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In re application of: Tu

Application Serial No.: 10/618,793

Filed: July 15, 2003

Method of Improving the Top-Plate Electrode Stress Inducting Voids for IT-RAM Process

Patent No.: Issue Date:

Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

CERTIFICATE UNDER 37 C.F.R. §3.73(b) ESTABLISHING RIGHT OF ASSIGNEE TO TAKE ACTION

The assignee of the entire right, title and interest hereby seeks to take action in the 1. PTO in this matter.

IDENTIFICATION OF ASSIGNEE

The assignee of this matter is: 2.

TAIWAN SEMICONDUCTOR MANUFACTURING CO., LTD.

8, Li-Hsin Rd. 6 Hsinchu Science Park Hsinchu, Taiwan 300-77, R.O.C.

PERSON AUTHORIZED TO SIGN

Daniel R. McClure 3. Attorney for Assignee

4.	A chair	n of title from the inventor(s) to the current assignee is shown below:						
	a.	From: Kuo-Chi TU To: Taiwan Semiconductor Manufacturing Co., Ltd. Recorded in PTO: Reel: 014298 Frame: 0644						
	b.	From: To: Recorded in PTO: Reel: Frame:						
DECLARATIONS								
5. I, the undersigned, have reviewed all the documents in the chain of title of the								
	\boxtimes	application patent						
matter ident	ove.	pove and, to the best of my knowledge and belief, title is in the assignee						
these statem	statements are ble by and th	reby declare that all statements made herein of my own knowledge are true, ents made on information and belief are believed to be true; and further, that is made with the knowledge that willful false statements, and the like so made, fine or imprisonment, or both, under Section 1001, Title 18 of the United hat such willful false statements may jeopardize the validity of the application ag thereon.						
7. behalf of th	I, th	e person signing below, aver that I am empowered to sign this statement on						
oonan or an								
		Daniel R. McClure, Reg. No. 38,962						
Tel. No. 7 Customer								
Docket No	o. 25201							



E UNITED STATES PATENT AND TRADEMARK OFFICE

in to Application. Application No.:

Filed: Title:

Commissioner for patents

Washington, D.C. 20231

POWER OF ATTORNEY BY ASSIGNEE OF ENTIRE INTEREST (REVOCATION OF PRIOR POWERS)

As assignee of record of each of the patent applications listed in the table of attachment A,

REVOCATION OF PRIOR POWERS OF ATTORNEY

all powers of attorney previously given in each of the listed patent applications are hereby revoked, and

NEW POWER OF ATTORNEY

the following attorneys/agents are hereby appointed to prosecute this application and to transact all business in the Patent and Trademark Office connected therewith: I hereby appoint all attorneys of Thomas, Kayden, Horstemeyer & Risley, LLP, who are listed under the USPTO Customer Number shown below as the attorneys to prosecute this application and to transact all business in the United States Patent and Trademark Office connected therewith, recognizing that the specific attorneys listed under that Customer Number may be changed from time to time at the sole discretion of Thomas, Kayden, Horstemeyer & Risley, LLP, and request that all correspondence about the application be addressed to the address filed under the same USPTO Customer Number.

24504

Patent Trademark Office

Please direct all future correspondence and telephone calls to:

Daniel R. McClure, Reg. No. 38,962 THOMAS, KAYDEN, HORSTEMEYER & RISLEY, L.L.P.

100 Galleria Parkway, Suite 1750 Atlanta, Georgia 30339 770-933-9500

ASSIGNEE OF ENTIRE INTEREST TAIWAN SEMICONDUCTOR MANUFACTURING COMPANY, LTD.

8, Li-Hsin Rd. 6 Hsinchu Science Park Hsinchu, Taiwan 300-77, R.O.C.

ASSIGNEE CERTIFICATION

The certification under 37 C.F.R. §3.73(b) establishing the right of assignee to take action is attached hereto along with documentation evidencing same. Further, in my official position with Taiwan Semiconductor Manufacturing Company, Ltd., I am authorized to sign documents and otherwise act on its behalf in connection with the management and handling of patent applications and other intellectual property matters.

June 29, 2004

Director - Intellectual Property Division

Attachment A

No.	Serial No	TSMC No.	Application Title	Filing Date	Assignment (Reel/Frame)
1	10/379,816	TS2001- 1414	Novel Formation of an Aluminum Contact Pad Free of Plasma Induced Damage by Applying	03/05/03	013849/0653
2	10/328,156	TS2001-	CMP A Method to Fabricate a Square Word Line Poly	12/23/02	013627/0309
	10/226,496	997/1115 TS2002-	Spacer Methodology to Characterize Metal Sheet	08/27/02	013236/0138
3 ——		0402 TS2002-	Resistance of Copper Damascena Process Method of Improving the Top Plate Electrode	07/15/03	014298/0644
4 !	10/618,793	1284 TS2001-	Stress Inducting Voids for IT-RAM Process	10/31/02	013454/0219
5	10/284,964	1045	Attenuating Phase Shifting Mask Material for 193	45-	
6	10/444,875	TS2000- 0763	Single Poly-SI Process for DRAM by Deep N	05/23/03	014114/0996
7	10/154,740	TS2001-	A Method of Fabricating an ESD Device on SOI	05/24/02	012934/0775
8	10/639,884	0672 TS2001- 748/774/82 2B	Novel Silicon-Controlled Rectifler Structures on Silicon-On Insulator with Shallow Trench Isolation	08/13/03	recorded 012798/0129 at the parent application US 6642088
9	D9/989,837	T\$2001-	RF Seal Ring Structure	11/20/01	012318/0614
10	10/696,430	0071 TS2000- 0680B	A Gate-Controlled, Negative Resistance Diode Device Using Band-to-Band Tunneling	10/29/03	recorded 012540/0729 s the parent application US 6657240
11	10/308,447	TS2001- 0921	Integrated Process Flow to Improve Copper Filling in a Damascene Structure	12/03/02	
12	10/224,215		A Structure and Fabricating Method with Self- Aligned Bit Line Contact to Word Line In Split Gate Flash	08/20/02	013217/0778

Chien-Wei (Chris) Chou Director - Intellectual Property Division